

# Hugues Vergnes

## List of Publications by Year in descending order

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Version: 2024-02-01

13  
papers

167  
citations

1306789

7  
h-index

1199166

12  
g-index

13  
all docs

13  
docs citations

13  
times ranked

192  
citing authors

#	ARTICLE	IF	CITATIONS
1	An innovative kinetic model allowing insight in the moderate temperature chemical vapor deposition of silicon oxynitride films from tris(dimethylsilyl)amine. Chemical Engineering Journal, 2022, 431, 133350.	6.6	4
2	Tunable SiO <sub>2</sub> to SiO <sub>x</sub> CyH films by ozone assisted chemical vapor deposition from tetraethylorthosilicate and hexamethyldisilazane mixtures. Surface and Coatings Technology, 2021, 407, 126762.	2.2	8
3	An innovative GC-MS, NMR and ESR combined, gas-phase investigation during chemical vapor deposition of silicon oxynitrides films from tris(dimethylsilyl)amine. Physical Chemistry Chemical Physics, 2021, 23, 10560-10572.	1.3	3
4	Network hydration, ordering and composition interplay of chemical vapor deposited amorphous silica films from tetraethyl orthosilicate. Journal of Materials Research and Technology, 2021, 13, 534-547.	2.6	4
5	Beyond surface nanoindentation: Combining static and dynamic nanoindentation to assess intrinsic mechanical properties of chemical vapor deposition amorphous silicon oxide (SiO <sub>x</sub> ) and silicon oxycarbide (SiO <sub>x</sub> Cy) thin films. Thin Solid Films, 2021, 735, 138844.	0.8	1
6	Large temperature range model for the atmospheric pressure chemical vapor deposition of silicon dioxide films on thermosensitive substrates. Chemical Engineering Research and Design, 2020, 161, 146-158.	2.7	9
7	Investigation of the initial deposition steps and the interfacial layer of Atomic Layer Deposited (ALD) Al <sub>2</sub> O <sub>3</sub> on Si. Applied Surface Science, 2019, 492, 245-254.	3.1	46
8	Î™n situ N <sub>2</sub> -NH <sub>3</sub> plasma pre-treatment of silicon substrate enhances the initial growth and restricts the substrate oxidation during alumina ALD. Journal of Applied Physics, 2019, 126, 125305.	1.1	6
9	Investigation of the densification mechanisms and corrosion resistance of amorphous silica films. Journal of Non-Crystalline Solids, 2019, 515, 34-41.	1.5	25
10	Detailed investigation of the surface mechanisms and their interplay with transport phenomena in alumina atomic layer deposition from TMA and water. Chemical Engineering Science, 2019, 195, 399-412.	1.9	35
11	Development of a kinetic model for the moderate temperature chemical vapor deposition of SiO <sub>2</sub> films from tetraethyl orthosilicate and oxygen. AIChE Journal, 2018, 64, 3958-3966.	1.8	9
12	Local Kinetic Modeling of Aluminum Oxide Metal-Organic CVD From Aluminum Triisopropoxide. Chemical Vapor Deposition, 2011, 17, 181-185.	1.4	15
13	Critical Level of Nitrogen Incorporation in Silicon Oxynitride Films: Transition of Structure and Properties, toward Enhanced Anticorrosion Performance. ACS Applied Electronic Materials, 0, , .	2.0	2